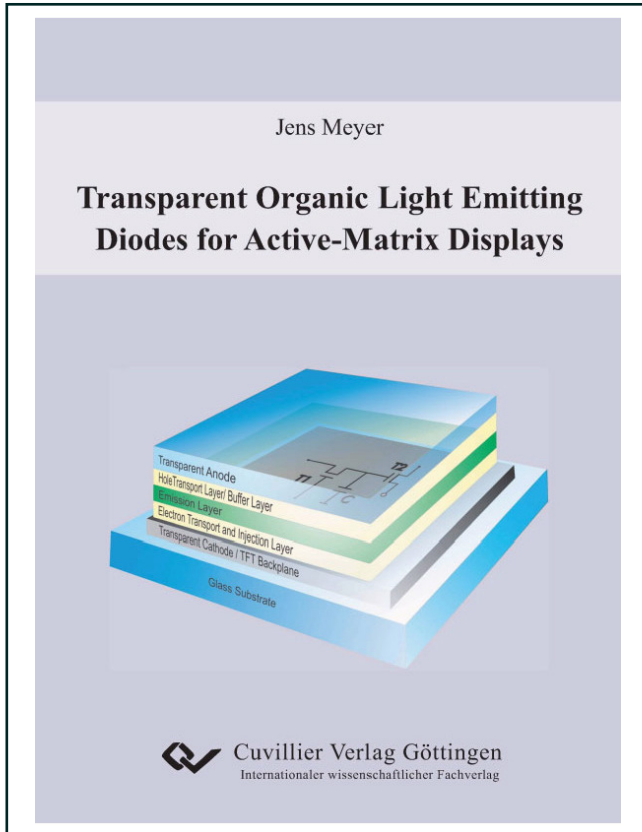




Jens Meyer (Autor)  
**Transparent Organic Light Emitting Diodes for  
Active-Matrix Displays**



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